MAPS for an ILC Si-W ECAL

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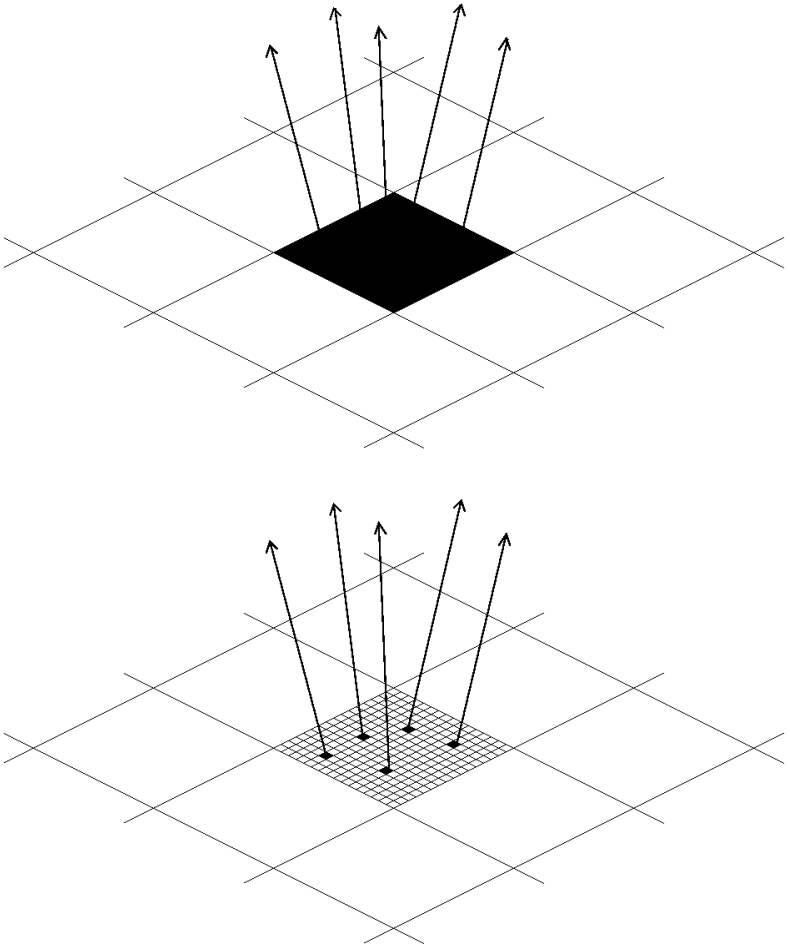
MAPS concept

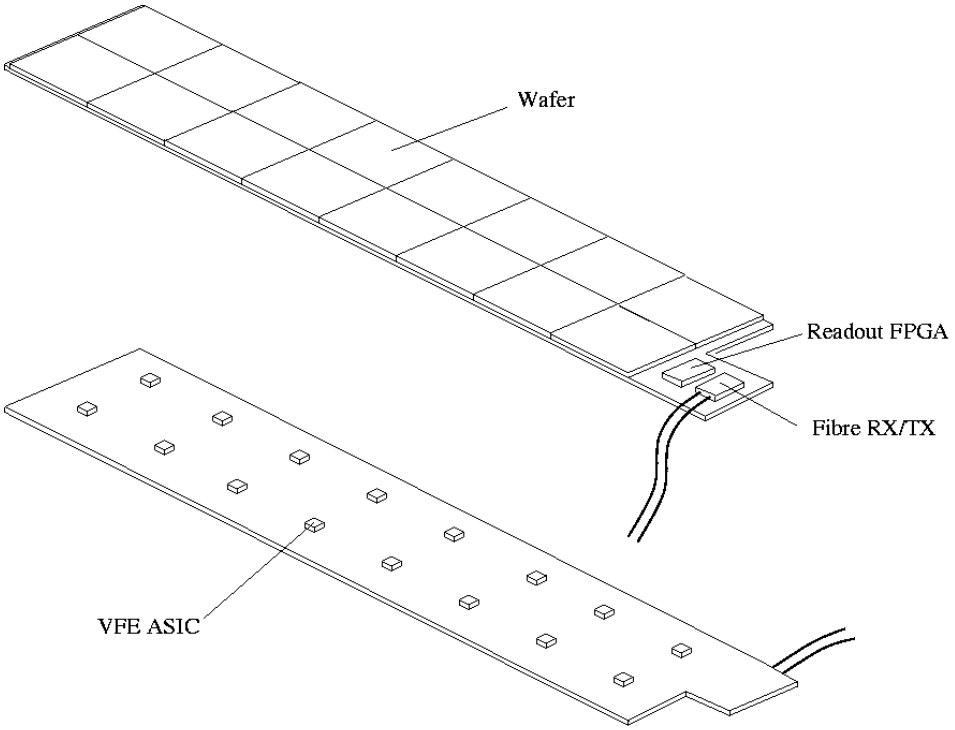
- Monolithic Active Pixel Sensors
  - Integrates readout electronics onto same wafer as sensitive detecting element
  - Uses standard CMOS technology, not high resistivity silicon as needed for Si-W ECAL with diode pads
- Charge detection through ionisation in the epitaxial layer
  - Can be very thin; ~5-10μm and close to the surface; ~few μm
  - Charge diffuses within epitaxial layer to metal contact
  - Read out via electronics constructed on surface above this layer
- Silicon wafers mechanically could be very similar to diode pads
  - Reuse almost all of diode pad mechanical structure ideas
  - "Simplest" approach would be to replace diode pad wafers with MAPS and integrate preamplifier (i.e. VFE ASIC circuit) into MAPS
- But this does not take full advantage of the new possibilities…

MAPS concept

- Readout concept is to go to a "digital" ECAL
  - Cover silicon in small pixels rather than diode pads
  - Use binary readout to keep data volume down
- "Small" means probability of more than one track per pixel is low
  - Density of EM shower @ 500 GeV ~100 MIPs/mm^2 in the core
  - Pixels have to be at most 100×100 μm^2 and probably more like 50×50 μm^2
  - Results in 40k pixels instead of each diode pad
  - Gives ~10^7 pixels/wafer and ~10^{12} pixels in total for the ECAL!
  - Only vaguely feasible because of highly integrated electronics

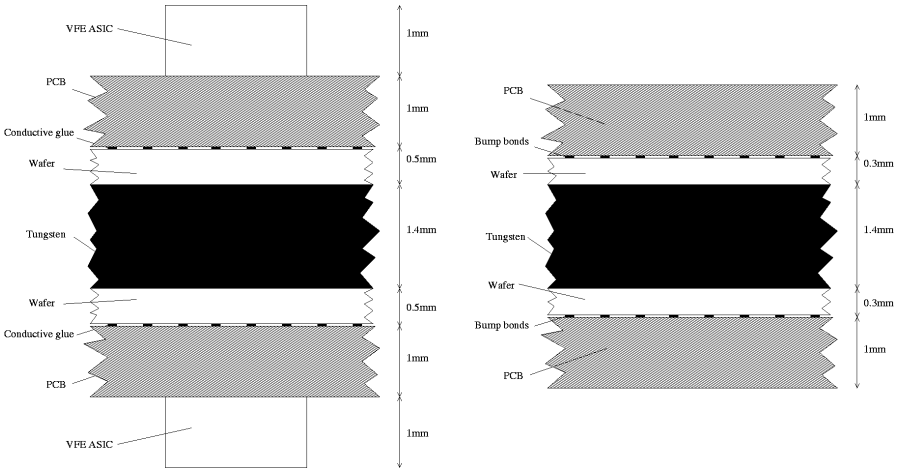


Comparison of MAPS with diode pads



- The PCB for both looks similar
  - But no VFE ASICs for MAPS case
- Wafer thickness can be reduced
  - Only epitaxial layer detects charge
  - Don't need full silicon thickness to get sufficient signal

- This changes the thickness of the total slab structure by ~2mm
  - Still smaller even if MAPS mounted double-sided on PCB



Two options

- Option 1: sum number of bits set over “pseudo-pad”
  - Area could be similar to original diode pad
  - Will give similar granularity
  - Difference is measurement is of number of particles, not deposited energy
  - Pixels act as “PDC” – Particle to Digital Converter!
  - Data rate per PCB ~3 Mbytes per bunch train
  - Interesting to know if sum area could be configurable or even event-by-event adaptive, depending on density of hits
- Option 2: read beam crossing timestamps indicating when bits set for every pixel
  - More ambitious; total possible information
  - Clearly more flexible; option 1 is calculable from the data read out
  - Gives extremely fine granularity for pattern recognition
  - Downside is data rate; factor of ~3 higher
  - This is probably the favoured option at present

Advantages compared with diode pads

- Energy measurement may be better
  - Pixels will measure the number of particles
  - Diodes measure the energy deposited in the silicon; depends on β and angle
  - David Ward's studies show ~10-20% improvement in resolution at lowish energies
- Granularity may be better (for option 2)
  - Two orders of magnitude improvement
  - Unclear how much is gained in actual PFLOW pattern recognition
- Effective Moliere radius may be smaller
  - No VFE ASIC means wafer PCBs are thinner by ~1mm per layer
  - Reduces inter-tungsten gap; again how significant for physics?
- Temperature stability may be better
  - Heat produced over whole wafer, not localised on VFE ASIC
  - Can use tungsten sheet as heat reservoir; bigger area for thermal coupling

Advantages (cont)

- Assembly may be easier
  - Single-sided PCB and no VFE ASIC
  - Bump-bonding (standard commercial process), not gluing for wafers
  - Reduces assembly steps; there will be ~5k PCBs in the ECAL!
- "Single event" upset may be reduced
  - Ionising particles can cause circuits to give corrupted results
  - Electronics will be hit by EM showers in both types of ECAL
  - Showers of order the Moliere radius ~9mm ~size of VFE ASIC so can affect whole chip
  - MAPS has much lower density of critical components
- COST!!!
  - Currently standard CMOS more than a factor two cheaper than high resistivity silicon

What we will bid for

- Three year programme to validate (or dismiss!) concept
  - Produce some prototype MAPS and test whether they work, in terms of signal size, noise rate, stability of threshold/pedestal, etc.
  - Ideally, put in a beam test for further checks, including single event upsets
  - Plan for two iterations of wafer manufacturing
  - These would be produced around 18 and 30 months into project
- First iteration will have several different designs
  - Around nine, each on a ~1×1 cm^2 (or smaller) area
  - Test various choices for comparator, readout, reset, etc.
- Second iteration will be a single design
  - Use modification of the best design from first iteration
  - Make 2×2 cm^2 area devices; standard commercial size
  - Would get standard run of six wafers, each holding ~ 50 sensors
  - Even allowing for bad yield, would be able to make several layers of e.g. 10×10 cm^2 area for a beam test

Simulation work is needed!

- Many of the arguments need firming up before proposal goes in
  - Need quantitative answers to many questions
  - First thing is to write a realistic simulation of a MAPS including the thin sensitive layer
- What pixel size is really needed?
  - Is $50\times50\ \mu m^2$ sufficient?
  - Would we see saturation effects from multiple tracks per pixel?
- What is the requirement on noise in the pixels?
  - How often can we tolerate a fake hit in a pixel?
  - Signal/noise of >10 could give 10^{-6} probability of fake hit, if Gaussian
  - Is one fake in every 10^6 samples good enough for physics?
  - This impacts both resolution on the shower energy and pattern recognition; which is the more critical?

Simulation work (cont)

- What is the actual improvement in using pixels not diode pads?
  - Preliminary studies on energy resolution started
  - Does the answer depend on the option chosen?
  - What about pattern recognition?
- What is a tolerable inefficiency per pixel?
  - The surface readout electronics may absorb some charge
  - May be a localised inefficiency; is this acceptable?
  - Does it affect resolution or pattern recognition more?
- What rate of crosstalk is acceptable?
  - Diffusion means tracks near pixel edges will share charge with neighbour
  - Better to have low threshold and hence two hits, or high threshold and hence zero hits?
  - What rate of sharing is tolerable?

Simulation work (cont)

- What is the rate from beam interactions in the pixels?
  - If too high, then the data volume would be prohibitive
  - TESLA TDR gives a rate of around each diode pad being above threshold once per train
  - How does this translate into pixels per train; 10 per diode? 100? 1000?
- What would be the difference in temperature stability?
  - Need thermal modeling rather than GEANT
  - Could make a difference between requiring cooling pipes or not?
- What improvement is achieved with a 1mm gap reduction?
  - Is this significant for shower separation?

Two months to answer as many of these questions as we can

- Please contact me if you want to help out here!